



High-precision photolithography and glass machining

PRODUCT DATASHEET

Film Photomask

SUBSTRATE & COATING

Material	Silver halide photographic emulsion coated on Polyester.
Substrate Thickness	0.18 mm (180 µm)

PATTERN & RESOLUTION

Minimum Feature	7 µm for line, 12µm for circle.
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DIMENSIONS

Dimensions	Up to 28x32 inches
Customized size	Custom size on request

USE CASES

Film photomasks are more affordable than glass masks, thus ideal for prototyping and relevant for numerous applications, including:

1	PCB
2	Semiconductors
3	MEMS
4	Microfluidics

HOW TO ORDER

Photomasks are made to order. Please provide the following information when requesting a quotation:

1	Mask dimensions
2	Minimum features size
3	Input data: GDS,CIF,DXF, Gerber 274
4	Required quantity and delivery timeframe



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Request a Quote

Contact us for custom glass photomask solutions tailored to your application and specifications.

selba.ch

** All values are nominal. Selba reserves the right to update specifications without prior notice. Custom tolerances and special requirements available on request.*